

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S11	1	(furnace near3 vapor adj phase with depositing and components and process adj gas and semiconductor adj substrate and space with receiving and first and feed same discharge adj line and process adj space and second adj feeds and discharge adj line and producing with process adj gas adj flow and heating adj device and regulating adj unit with regulating with magnitude and flow near3 direction). clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:25

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	10	("5484484" "6045617" "6074202" "6184049" "6579374").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 09:58
S2	60	("5484484" "6045617" "6074202" "6184049" "6579374")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:01
S3	1	10/675049	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:16
S4	9331	438/14,714,706,729,758,761,791.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:02
S5	5929	118/119,715.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:02
S6	15156	S4 S5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:08
S8	222	S6 and (vapor adj phase near3 deposit\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:12

EAST Search History

S9	32	S6 and (vapor adj phase near3 deposit\$3) and measuring	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:12
S10	132338	(furnace near3 vapor adj phase with depositing and components and process adj gas and semiconductor adj substrate and space with receiving and first feed same discharge adj line and process adj space and second feeds ame discharge adj line and producing with process adj gas adj flow and heating adj device and regulating adj unit with regulating with magnitude and flow near3 direction). clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:21
S11	1	(furnace near3 vapor adj phase with depositing and components and process adj gas and semiconductor adj substrate and space with receiving and first and feed same discharge adj line and process adj space and second adj feeds and discharge adj line and producing with process adj gas adj flow and heating adj device and regulating adj unit with regulating with magnitude and flow near3 direction). clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/21 10:25